

The AIChE JOURNAL, a monthly publication of the American Institute of Chemical Engineers, is devoted to fundamental research and developments having immediate or potential value in chemical engineering.

EDITOR

Morton M. Denn

MANAGING EDITOR

Haeja L. Han

EDITORIAL ASSISTANTS

Debra E. Soltanoff
Karen M. Simpson

CONSULTING EDITORS

Richard Alkire
Electrochemical Engineering

Bruce Finlayson
Computation

Joe D. Goddard
Transport Processes

Louis Hegedus
Catalysis/Surface Science

Sheldon Isakoff
Materials

Roy Jackson
Transport Processes

George E. Keller, II
Separations

John Riggs
Materials

Stanley Sandler
Thermodynamics

John Seinfeld
Aerosols/Atmospheric Science

Reuel Shinnar
Reaction Engineering

Michael Shuler
Biochemical Engineering

George Stephanopoulos
Systems/Design

Larry F. Thompson
Electronic Materials

PUBLICATIONS DIRECTOR

Diane Foster

New Proceedings

Processing of Electronic Materials

Clarence G. Law, Jr. & Richard Pollard, Editors
(Proceedings of the First International Conference, Santa Barbara, California, February 23-28, 1987, Sponsored by the Engineering Foundation)

These conference papers present viewpoints from the academic and industrial communities. Factors that determine the behavior of processes used to manufacture electronic materials are addressed. Emphasis is on current and future scientific methods for understanding and solving critical processing problems. Various approaches for relating process conditions to product properties are discussed as well as design modifications and novel techniques for improving thin film quality, productivity, and system reliability. Challenges facing the processing of new devices are described in addition to the evaluation of relative merits of different processes.

SUBJECTS COVERED

Chemical Vapor Deposition. Silicon. Semiconductors. Plasma Processes. Dielectrics. Physical Vapor Deposition. Characterization. Liquid Phase Processes. Purification of Chemicals. Metals and Metal Silicides. Future Trends in Electronic Materials Processing.

1987 488 pp ISBN 0-8196-0427-8 LC87-81560

Pub P-50 Hardcover AIChE Members \$40 Others \$60

SEND BOOK ORDERS to: AIChE Publication Sales Dept.
345 East 47 Street, New York, NY 10017.

Prepayment in U.S. currency is required. Prices subject to change. All sales are final.

AIChE Journal (ISSN 0001-1541) is published monthly by the American Institute of Chemical Engineers, 345 E. 47th St., New York, NY 10017. Manuscripts should be submitted to Editor Morton M. Denn, at the Dept. of Chemical Engineering, University of California, Berkeley, CA 94720, Phone (415) 643-6591. The statements and opinions in the *AIChE Journal* are those of the contributors, and AIChE assumes no responsibility for them. Annual subscription rates: \$275 for nonmembers, \$40 for members; outside U.S., add \$13 for postage. Single copies: \$30; outside U.S., add \$2 for postage. Second-class postage paid at New York, NY and additional mailing offices. Copyright 1988 by the American Institute of Chemical Engineers. Subscribers are requested to give prompt notification of any change of address. Postmaster: Send changes of address to *AIChE Journal*, 345 East 47th St., New York, NY 10017.

Authorization to photocopy items for internal or personal use, or the internal or personal use of specific clients, is granted by AIChE for libraries and other users registered with the Copyright Clearance Center (CCC) Transactional Reporting Service, provided that the \$3.00 per copy fee is paid directly to CCC, 21 Congress St., Salem, MA 01970. This consent does not extend to copying for general distribution, for advertising or promotional purposes, for inclusion in a publication, or for resale. Articles published before 1988 are subject to the same copyright conditions and the fee for each article is \$2.00. *AIChE Journal* fee code: 0001-1541/88 \$3.00.